

369520919

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Priority APPLICATION SERIAL NO. .... 08/984,730  
Priority FILING DATE ..... December 4, 1997  
INVENTORSHIP ..... D.G. Custer et al.  
ASSIGNEE ..... Micron Technology, Inc.  
Priority GROUP ART UNIT ..... 3723  
Priority EXAMINER ..... L. Wilson  
ATTORNEY'S DOCKET NO. .... MI22-1172  
TITLE: Polishing Systems, Methods of Polishing Substrates, and Methods of Preparing  
Liquids for Semiconductor Fabrication Processes

Assistant Commissioner for Patents  
Washington, D. C. 20231  
Attention: Official Draftsman

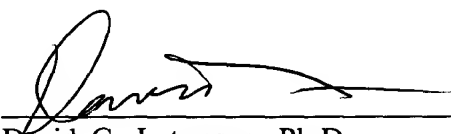
**SUBSTITUTE DRAWING REQUEST**

Please enter the enclosed substitute drawings in the above-referenced application in place of drawings originally filed. The content of the drawings are identical to those now on file in this application.

Acknowledgment of receipt of the formal drawings and their acceptance into the file is requested.

Respectfully submitted,

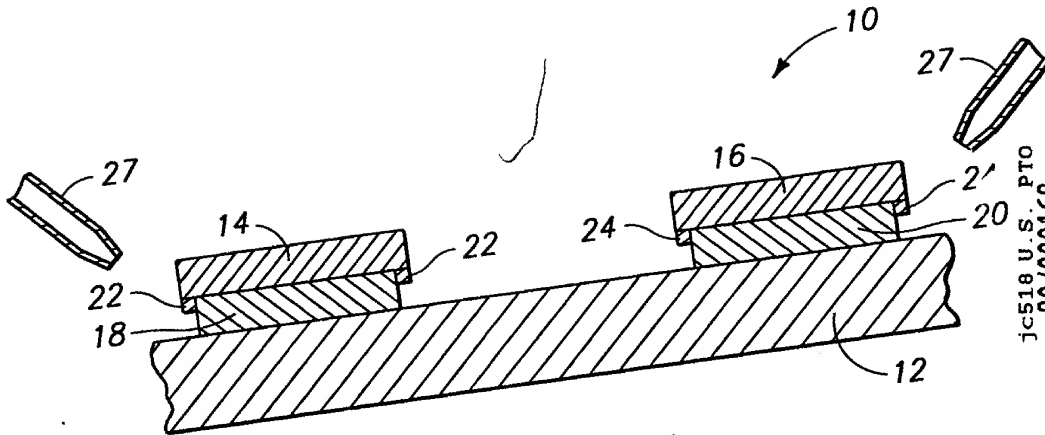
Date: 4/22/99

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Enclosures: 2 Sheets of Formal Drawings, Figs. 1-3.

AS FILED

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FIG. 1

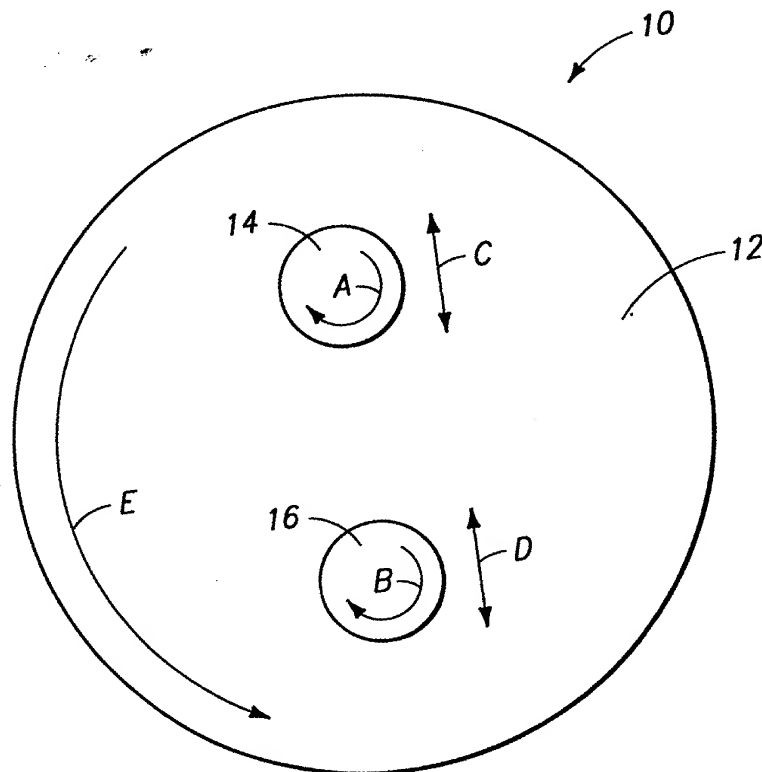


FIG. 2

